

- 1 1. A photoresist comprising:
2 a photoacid generator that is more transparent
3 than phenyl containing photoacid generators.
- 1 2. The photoresist of claim 1 including an anion and
2 a cation, wherein said cation does not include phenyl.
- 1 3. The photoresist of claim 1 wherein said photoacid
2 generator includes a cation that is sigma-bonded.
- 1 4. The photoresist of claim 1 wherein said photoacid
2 generator includes a cation with a base atom coupled to at
3 least one sigma-bonded moiety.
- 1 5. The photoresist of claim 1 wherein said photoacid
2 generator includes a cation with a base atom coupled to at
3 least two sigma-bonded moieties.
- 1 6. The photoresist of claim 1 wherein said photoacid
2 generator includes a cation with a first moiety sigma-
3 bonded to a base atom and a chain coupled to said base
4 atom, said chain in turn coupled by a double bond to second
5 moiety.

1 7. The photoresist of claim 6 wherein said second
2 moiety is selected from the group of carbon, nitrogen,
3 sulfur, and phosphorus.

1 8. The photoresist of claim 7 wherein said second
2 moiety is coupled to an alkyl or a substituted alkyl.

1 9. The photoresist of claim 8 wherein said alkyl or
2 substituted alkyl includes a halogen, ether, ester,
3 carbonate, or ketone.

1 10. The photoresist of claim 1 including a photoacid
2 generator including a cation including a base atom coupled
3 to at least two moieties by sigma-bonds, said base atom
4 coupled to a chain in turn coupled to a first moiety, said
5 first moiety coupled through a double bond to a second
6 moiety.

1 11. The photoresist of claim 10 wherein said second
2 moiety and said first moiety are selected from the group
3 including carbon, nitrogen, sulfur, and phosphorus.

1 12. The photoresist of claim 11 wherein at least one
2 of said first and second moieties includes oxygen.

1 13. The photoresist of claim 10 wherein said base
2 atom is sulfur.

1 14. A method comprising:
2 forming a photoresist with a photoacid generator
3 that is more transparent than phenyl containing photoacid
4 generators.

1 15. The method of claim 14 including providing a
2 cation to said photoacid generator that does not include
3 phenyl.

1 16. The method of claim 14 including providing a
2 sigma-bonded cation.

1 17. The method of claim 14 including forming said
2 photoacid generator of a cation with a base atom coupled to
3 at least one sigma-bonded moiety.

1 18. The method of claim 14 including forming said
2 photoacid generator with a cation having a base atom
3 coupled to at least two sigma-bonded moieties.

1 19. The method of claim 14 including forming said
2 photoacid generator with a cation having a first moiety
3 sigma-bonded to a base atom and a chain coupled to said
4 base atom, coupling said chain by a double bond to a second
5 moiety.

1 20. The method of claim 19 including forming said
2 second moiety from carbon, nitrogen, sulfur, or phosphorus.

1 21. The method of claim 20 including forming said
2 second moiety of an alkyl or substituted alkyl.

1 22. The method of claim 14 including forming the
2 photoacid generator with a cation having a base atom
3 coupled to at least two moieties by sigma-bonds, said base
4 atom coupled to a chain in turn coupled to a first moiety,
5 said first moiety coupled through a double bond to a second
6 moiety.

1 23. A photoresist comprising:
2 a photoacid generator including a cation that is
3 entirely sigma-bonded.

1 24. The photoresist of claim 23 wherein said cation
2 includes a base atom coupled by sigma-bonds to at least
3 three moieties.

1 25. The photoresist of claim 23 wherein said moieties
2 are alkyl or substituted alkyls.

1 26. The photoresist of claim 25 wherein said alkyl or
2 substituted alkyl includes a halogen, ether, ester,
3 carbonate, or ketone.

1 27. The photoresist of claim 23 wherein said
2 photoacid generator includes a sulfur atom sigma-bonded to
3 alkyl groups.

1 28. The photoresist of claim 24 wherein said base
2 atom is sulfur.